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## Remarks:

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## (54) COIL TOPOLOGIES FOR INDUCTIVE POWER TRANSFER

(57) This disclosure provides systems, methods and apparatus including a magnetic flux device configured to transmit or receive magnetic flux. In certain configurations, the magnetic flux device can include a first coil with a first layer and second layer, a second coil with a third layer and fourth layer, and a magnetically permeable material with the first coil extending over a first edge of the magnetically permeable material and the second coil extending over a second edge of the magnetically perme-

able material. In certain other configurations, the magnetic flux device can include a first conductive structure including a first coil and a second coil enclosing a first area and a second area, respectively. The magnetic flux device can further include a second conductive structure with at least a first planar portion of the first conductive structure being substantially coplanar with a second planar portion of the second conductive structure.

